- (132) (Electron near3 beam) and (hierarch$5 near3 data)
- (856) 716/19
- (2) 716/19 and (residual near3 data)
- (22) 716/19 and (beam near3 control)
- (22) (716/19 and (beam near3 control)) not (716/19 and (residual near3 data))
- (8) "6047116" "6189135"
- (1) "5526279".PN.
- (3) 6047116.URPN.
- (1) (electron near3 beam) and (pattern near3 generation) and hierarch$5 and (residual near4 data)
- (2) (electron near3 beam) and (pattern near3 generation) and (residual near4 data)
- (2) "6543044"
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